Electronic Supplementary Material (ESI) for RSC Advances

## Tuning the morphology of Co<sub>3</sub>O<sub>4</sub> on Ni foam for

## supercapacitor application

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**Figure S1** XRD pattern of the Co<sub>3</sub>O<sub>4</sub>-1 precursor

(scratched from Ni foam after 6 h hydrothermal reaction).



**Figure S2** XRD patterns of the Co<sub>3</sub>O<sub>4</sub>-2, Co<sub>3</sub>O<sub>4</sub>-3, and Co<sub>3</sub>O<sub>4</sub>-4 precursors (scratched from Ni foam after 6 h hydrothermal reaction)



**Figure S3** FTIR spectrum of the Co<sub>3</sub>O<sub>4</sub>-1 precursor (scratched from Ni foam after 6 h hydrothermal reaction).



**Figure S4** Optical images of precursors of  $Co_3O_4$ -1,  $Co_3O_4$ -2,  $Co_3O_4$ -3, and  $Co_3O_4$ -4 (left to right) (a); optical images of  $Co_3O_4$ -1,  $Co_3O_4$ -2,  $Co_3O_4$ -3, and  $Co_3O_4$ -4 (left to right) (b).



Figure S5 CV curves of  $Co_3O_4$ -1 (a),  $Co_3O_4$ -2 (b),  $Co_3O_4$ -3 (c), and  $Co_3O_4$ -4 (d) at various scan rates.



Figure S6 CV curves of bare Ni foam, 6 M hydrochloric acid treated Ni foam and  $Co_3O_4$ -2 at 5 mV s<sup>-1</sup> scan rate.



Figure S7 XRD patterns of 6 M hydrochloric acid treated Ni foam



**Figure S8** Ni 2p XPS spectra of 6 M hydrochloric acid treated Ni foam (a), O 1s XPS spectra of 6 M hydrochloric acid treated Ni foam (b).



**Figure S9** Charge and discharge curves of  $Co_3O_4$ -1 (a),  $Co_3O_4$ -2 (b),  $Co_3O_4$ -3 (c), and  $Co_3O_4$ -4 (d) at various current densities.

Table S1 Comparison of values for the specific area capacitance in previously reported wor	rks on
supercapacitors with values for the four Co <sub>3</sub> O <sub>4</sub> materials presented here.	

Material	Specific area capacitance (F cm <sup>-2</sup> )	Reference
Co <sub>3</sub> O <sub>4</sub>	$0.68 (4.2 \text{ mA/cm}^2)$	<b>S</b> 1
Co <sub>3</sub> O <sub>4</sub> @NiO	1.35 (6 mA/cm <sup>2</sup> )	51
Co <sub>3</sub> O <sub>4</sub>	$0.135 (11.25 \text{ mA/cm}^2)$	S2
Co <sub>3</sub> O <sub>4</sub> @MnO <sub>2</sub>	0.56 (11.25 mA/cm <sup>2</sup> )	
CoO	$0.285 (5 \text{ mA/cm}^2)$	<b>S</b> 3
CoO@PPy	2.51 (5 mA/cm <sup>2</sup> )	
Co <sub>3</sub> O <sub>4</sub>	0.79 (5 mV/s)	S4
Co <sub>3</sub> O <sub>4</sub> @NiCo <sub>2</sub> O <sub>4</sub>	2.04 (5 mV/s)	
NiCo <sub>2</sub> O <sub>4</sub>	$0.84 (2 \text{ mA/cm}^2)$	

NiCo <sub>2</sub> O <sub>4</sub> @NiCo <sub>2</sub> O <sub>4</sub>	$1.55 (2 \text{ mA/cm}^2)$	
MnO <sub>2</sub>	$0.101 (8.5 \text{ mA/cm}^2)$	56
MnO <sub>2</sub> @NiO	$0.35 (8.5 \text{ mA/cm}^2)$	30
NiCo <sub>2</sub> O <sub>4</sub>	$1.5 (8.5 \text{ mA/cm}^2)$	\$7
NiCo <sub>2</sub> O <sub>4</sub> @MnO <sub>2</sub>	$2.54(8.5 \text{ mA/cm}^2)$	57
Co <sub>3</sub> O <sub>4</sub> -1	$0.5 (5 \text{ mA/cm}^2)$	This work
Co <sub>3</sub> O <sub>4</sub> -2	$1.92 (5 \text{ mA/cm}^2)$	This work
Co <sub>3</sub> O <sub>4</sub> -3	$1.53 (5 \text{ mA/cm}^2)$	This work
Co <sub>3</sub> O <sub>4</sub> -4	0.87 (5 mA/cm <sup>2</sup> )	This work



**Figure S10** Electrochemical impedance spectroscopy plots of  $Co_3O_4$ -1,  $Co_3O_4$ -2,  $Co_3O_4$ -3, and  $Co_3O_4$ -4 before cycling (a), after 3000 cycles (b), and equivalent circuit (c).



Figure S11 Bode plots of Co<sub>3</sub>O<sub>4</sub>-1, Co<sub>3</sub>O<sub>4</sub>-2, Co<sub>3</sub>O<sub>4</sub>-3, and Co<sub>3</sub>O<sub>4</sub>-4.

## **References:**

- S1 X. Xia, J. Tu, Y. Zhang, X. Wang, C. Gu, X. B. Zhao and H. J. Fan, *ACS Nano*, 2012, 6, 5531-5538.
- S2 J. Liu, J. Jiang, C. Cheng, H. Li, J. Zhang, H. Gong and H. J. Fan, Adv Mater, 2011, 23, 2076-2081.
- S3 C. Zhou, Y. Zhang, Y. Li and J. Liu, Nano Lett, 2013, 13, 2078-2085.
- S4 G. Zhang, T. Wang, X. Yu, H. Zhang, H. Duan and B. Lu, Nano Energy, 2013, 2, 586-594.
- S5 X. Liu, S. Shi, Q. Xiong, L. Li, Y. Zhang, H. Tang, C. Gu, X. Wang and J. Tu, ACS Appl Mater Interfaces, 2013, 5, 8790-8795.
- S6 J. Liu, J. Jiang, M. Bosman and H. J. Fan, J Mater Chem, 2012, 22, 2419-2426.
- S7 L. Yu, G. Zhang, C. Yuan and X. W. Lou, Chem Commun, 2013, 49, 137-139.